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- AN - 1996-405795 [41]
- TI - Photomask using photo lithography for wiring pattern of electric circuit - in which negative pattern or positive pattern of electric circuit is formed by performing photograph etching or screen printing to film like member
- AB - J07319146 The photomask has a film like member (4) with resin composition and is deformed by heat and pressure. The film like member is formed corresponding to compact having 3D structure. Negative pattern (5) or positive pattern of electric circuit is formed by performing photograph etching or screen printing to film like member.
- ADVANTAGE - Improves mfr efficiency of wiring object.
- (Dwg.1/5)
- IW - PHOTOMASK PHOTO LITHO WIRE PATTERN ELECTRIC CIRCUIT NEGATIVE PATTERN POSITIVE PATTERN ELECTRIC CIRCUIT FORMING PERFORMANCE PHOTOGRAPH ETCH SCREEN PRINT FILM MEMBER
- PN - JP7319146 A 19951208 DW199641 G03F1/00 005pp
- IC - G03F1/00 ; G03F1/14 ; H05K3/00 ; H05K3/06 ; H05K3/18
- MC - A12-L02A G06-D06 G06-E02 G06-G G06-G18 L03-H04E2
- V04-R01B V04-R02
- DC - A89 G06 L03 P84 V04
- PA - (HITD) HITACHI CABLE LTD
- AP - JP19940112791 19940526
- PR - JP19940112791 19940526